

## Cr Photomasks

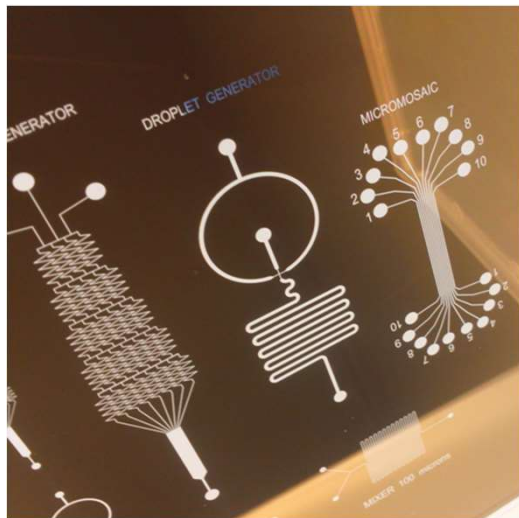
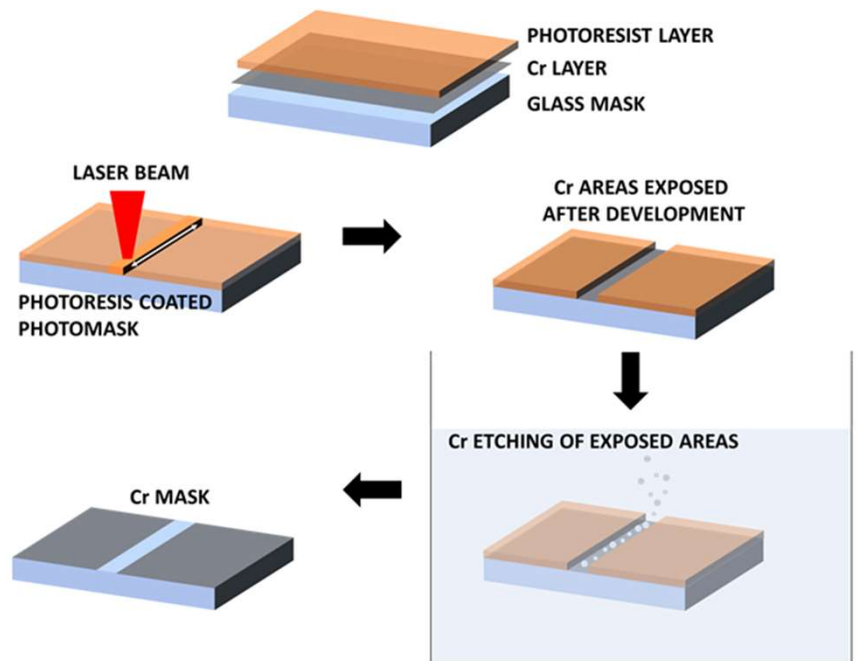
In the MicroFabSpace we fabricate 5 inches chromium photomasks, with resolution as small as 1 μm for UV photolithography processes. The fabrication of high-resolution photomasks in-house, allows to speed up critical processes requiring masking, at competitive cost and to have direct assistance in design for the targeted application.

### A process of photomask making starts

with a Cr-coated glass mask, which is covered by a thin layer of positive photoresist.

The coated photomask is exposed to a 405 nm laser source that draws the pattern directly on the photoresist.

The pattern is created by a mask making software, as AutoCAD for instance, which is compatible with the laser controller software. After laser lithography development, the exposed chromium areas are removed by wet etching. Finally, the remaining photoresist that protects the rest of Cr of the mask is removed, revealing the pattern of the mask.



Cr Mask for the fabrication of microfluidic devices.

The mask contains multiple designs for different applications.